



# Together with new optics, ECLIPSE is evolving to the next stage.

Modularized to meet industrial microscope applications in diverse fields of industry, including semiconductor devices, packaging, FPDs, electronic components, materials, and precision molds.

The ECLIPSE LV Series continues to evolve while offering various stand and illumination units selectable according to the observation method and purpose.

Four types – motorized and manual types plus dedicated reflected illumination and combined reflected/ transmitted illumination types – are available to meet any application.

# Illuminators

## **Expanded lineup**

Added a compact LED illuminator to the existing lineup.

With the use of LED, Nikon illuminators are power saving and achieve long life.



## **Evolved optical performance**

Nikon's CFI<sub>60</sub> optical system, highly evaluated for its unique concept of high NA combined with long working distance has further evolved to achieve the apex in long working distance, chromatic aberration correction, and light weight.

# Easy Operation

## Combination with digital camera

Detection of microscope information, including objective lens information, and motorized unit microscope operation are now possible using imaging software, for more efficient observation and image capture.

# Observation Methods

## **Diverse observation / optical contrast methods**

Combinations of a full range of accessories expand the observation methods available when using transmitted illumination, allowing adaptability to a greater diversity of samples.

All models enable brightfield, darkfield, differential interference, fluorescence, polarizing, and two-beam interferometry observation, while the LV100ND LED and LV100NDA LED also allow transmission-type differential interference, darkfield, polarizing, and phase contrast observation.



# LV-N Series

#### **Model features**







LV150NA

Motorized type

(Nosepiece)



LV100ND LED



LV100NDA LED

#### **Dedicated reflected illumination models**

Microscope type

Compatible

observation methods

Compatible stages

Integration with Digital Sight cameras for microscopes

Manual type

	Brightfield	Darkfield	DIC	Fluorescence	Polarizing	Two-beam Interferometry
Episcopic	0	0	0	0	0	0
Episcopic (LED)	0	0	0	_	Δ	_

- \* Use an objective lens appropriate to the observation method. △: only simple polarizing observation
  - LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) \*Can be fitted with LV-S32SPL ESD plate
  - LV-S6 6x6 stage (Stroke: 150 x 150 mm) \*Can be fitted with LV-S6WH wafer holder / LV-S6PL ESD plate
  - LV-SRP P revolving stage

#### Digital Sight 10 or DS-Fi3 or Digital Sight 1000\*

 Objective lens information detection\*\* (when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

Objective lens information detection and control\*\*



Manual type

#### Motorized type

(Nosepiece / light intensity / aperture stop / observation method selector)

	Brightfield	Darkfield	DIC	Fluorescence	Polarizing	Two-beam Interferometry	Phase- contrast
Episcopic	0	0	0	0	0	0	
Diascopic	0	0	0	_	0	_	0

Combined reflected/transmitted illumination models

- \* Use an objective lens appropriate to the observation method.
  - LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) \*Can be fitted with LV-S32SGH slide glass holder
  - LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate)
  - LV-SRP P revolving stage
  - NIU-CSRR2 Ni-U right handle rotatable ceramic stage (Stroke: 78 x 54 mm)
  - C-CSR2S right handle stage (Stroke: 78 x 54 mm: Used with stage adapter LV-SAD)

#### Digital Sight 10 or DS-Fi3 or Digital Sight 1000\*

Objective lens information detection\*\* (when used with combination of Intelligent Nosepiece LV-NU5I and LV-INAD)

 Information detection and control of objective lens, light intensity, aperture stop, and observation method (brightfield / darkfield / fluorescence)\*\*

Elements

Note: \*With imaging software NIS-Elements L and F, functions above are not available. Use NIS-Elements D/Br/Ar. \*\*Excluding Digital Sight 1000

## **Evolved optical performance**

Nikon's CFI60 optical systems are highly evaluated for their unique concept of high NA combined with a long working distance. These lenses have been developed further and evolved achieving the apex in long working distance specifications, correct chromatic aberration, and an optimized lens weight.

#### T Plan & TU Plan Fluor & TU Plan Apo Lenses

Standard Plan objective lenses

Standard objective lenses

## TU Plan Fluor Series

EPI/BD 5x/10x/20x/50x/100x

Enable brightfield, darkfield, simple polarizing, sensitive polarizing, differential interference, and epi-fluorescence observations with just one lens. Achieves superior chromatic aberration performance with long working distance for all magnifications to adapt to any application.











\*Brightfield observation (EPI) objective lens

Model	Magnification	NA	Working Distance (mm)
TU Plan Fluor EPI	5×	0.15	23.5
(brightfield type)	10×	0.30	17.5
	20×	0.45	4.5
	50×	0.80	1.0
	100×	0.90	1.0
TU Plan Fluor BD	* 5×	0.15	18.0
(brightfield/darkfield type)	* 10×	0.30	15.0
	* 20×	0.45	4.5
	50×	0.80	1.0
	100×	0.90	1.0

<sup>\*</sup> Uses fly-eye lens.

Low-magnification objective lenses

## T Plan EPI

EPI 1x/2.5x

Both clear observation using a conventional analyzer/polarizer and operability-oriented observation without the need of an analyzer/ polarizer are possible.



Model	Magnification	NA	Working Distance (mm)
T Plan EPI	1×	0.03	3.8
(brightfield type)	2.5×	0.075	6.5

# EPI/BD 50x/100x/150x

By using phase Fresnel lenses, these objective lenses achieve significantly longer operating distances while maintaining the superior chromatic aberration performance of apochromatic



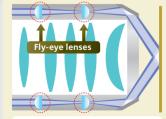
\*Brightfield observation (FPI) objective lens

Model	Magnification	NA	Working Distance (mm)
TU Plan Apo EPI	50×	0.8	2.0
(brightfield type)	100×	0.9	2.0
	150×	0.9	1.5
TU Plan Apo BD	50×	0.8	2.0
(brightfield/darkfield type)	100×	0.9	2.0
	150×	0.9	1.5

# Dark Field Illumination

#### Fly-eye lens

Through the use of fly-eye lenses, the CFI60-2 optical system offers bright darkfield illumination throughout the field of view with little unevenness, even for lowmagnification lenses.

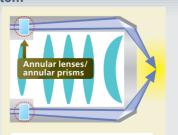


Fly-eye lenses adjust the diffusion angle of light so light strikes the focal

#### Darkfield illumination system ·····

As NA and WD improve, objective lenses increase in outside diameter. However, as the width of incident light is fixed, light intensity decreases with conventional illumination systems. The illumination system uses annular lenses or annular prisms to increase captured light and achieve bright darkfield illumination with no

deterioration.



#### Annular lenses/prisms take in more light to increase brightness

## TU Plan ELWD & T Plan SLWD Lenses

Long working distance objective lenses



With the phase Fresnel lenses, these objective lenses enable long working distances while offering higher level chromatic aberration correction than conventional objective lenses. This improves operability for samples with different heights.





I	Working Distance (mm)	

Model	Magnification	NA	Working Distance (mm)
T Plan EPI	1×	0.03	3.8
(brightfield type)	2.5×	0.075	6.5

#### Apochromatic objective lenses

# TU Plan Apo Series



	Magnification	NA	Working Distance (mm)
	50×	0.8	2.0
	100×	0.9	2.0
	150×	0.9	1.5
	50×	0.8	2.0
d type)	100×	0.9	2.0

# TU Plan ELWD Series





Model	Magnification	NA	Working Distance (mm)
TU Plan EPI ELWD	20×	0.4	19.0
(brightfield type)	50×	0.6	11.0
	100×	0.8	4.5
TU Plan BD ELWD	20×	0.4	19.0
(brightfield/darkfield type)	50×	0.6	11.0
	100×	0.8	4.5

## Super-long working distance objective lenses

## T Plan EPI SLWD

EPI 10x/20x/50x/100x

Improving on chromatic aberration

while prioritizing working distance, the T Plan SLWD Series achieve

the best-in-class super-long

working distance. The SLWD

10x (WD: 37 mm) lens enables

use with a greater diversity of

samples.



Long working distance / Super-long working distance objective lenses









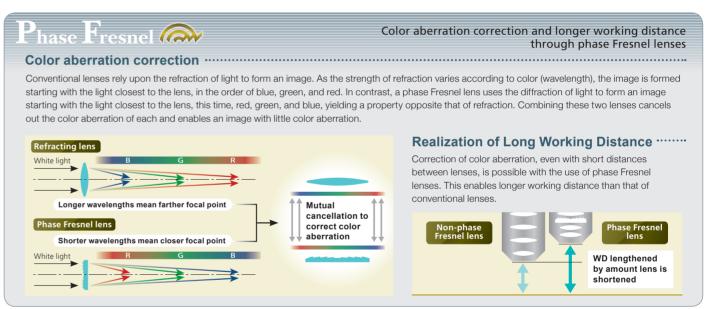








Model	Magnification	NA	Working Distance (mm)
T Plan EPI SLWD	10×	0.2	37.0
(brightfield type)	20×	0.3	30.0
	50×	0.4	22.0
	100×	0.6	10.0



## Other lenses

Objective lenses with glass thickness correction features

#### CFI L Plan EPI CR 20x/50x/100x

Equipped with corrective features that enable high contrast observation of cells or patterns, these observation lenses are unaffected by the glass substrate.



Model	Magnification	NA	Working Distance (mm)
CFI L Plan EPI CR	20× CR	0.45	10.90 - 10.00
(brightfield type)	50× CR	0.70	3.90 - 3.00
	100× CRA	0.85	1.20 - 0.85
	100× CRB	0.85	1.30 - 0.95

Objective lenses for brightfield observation

### CFI LE Plan EPI **EPI** 5x/10x/20x/50x/100x







Model	Magnification	NA	Working Distance (mm)
LE Plan EPI	5×	0.1	31.0
(brightfield type)	10×	0.25	13.0
	20×	0.4	3.6
	50×	0.75	0.5
	100×	0.9	0.31

# **Easy Operation**

#### Combination with digital camera

## LV150N / LV150NA / LV100ND LED

Objective lens information detection and control

Information about the objective lens being used can be detected when combining the Intelligent Nosepiece LV-NU5I and the Nosepiece Adaptor LV-INAD. The information is automatically converted to appropriate calibration data when changing the magnification.

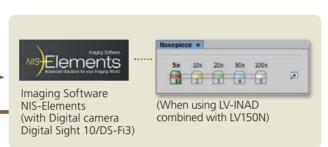
In addition, the LV150NA allows switching of objective lenses via the imaging software.







LV-INAD Nosepiece Adaptor

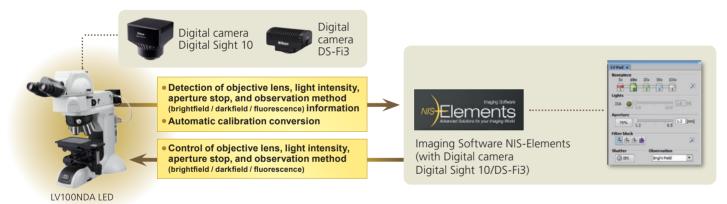


LV150N / LV150NA / LV100ND LED

## LV100NDA LED

#### Microscope information detection and control

The LV100NDA LED allows detection of information and control of objective lenses, light intensity, aperture stop, and observation method (brightfield / darkfield / fluorescence) via the imaging software, enabling optimization of the conditions vital for image acquisition.



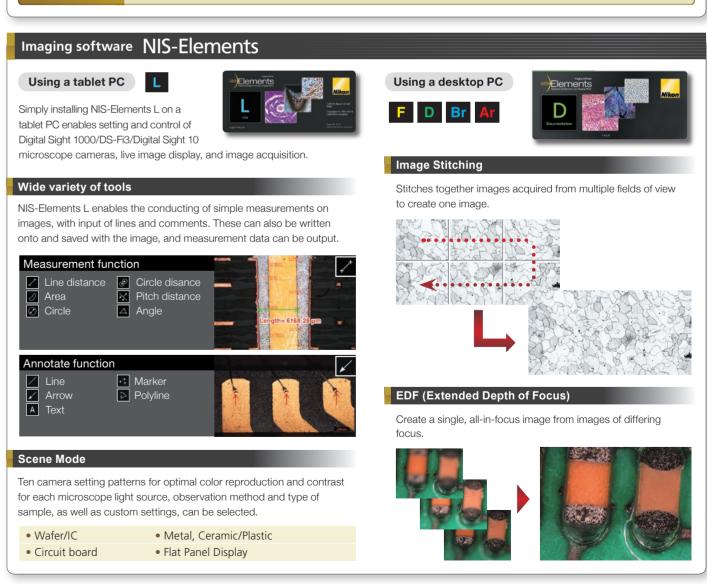
Information detection and control possible     Information detection only	LV150N/LV100ND LED (When using LV-NU5I and LV-INAD)	LV150NA	LV100NDA LED (When using LV-UEPI2A Illuminator	
O. Information detection only	Digital Sight 10/DS-Fi3 (+NIS-Elements)	Digital Sight 10/DS-Fi3 (+NIS-Elements)	Digital Sight 10/DS-Fi3 (+NIS-Elements	
Objective lens		<b>©</b>	(i)	
Reflected illumination *When using (ON/OFF, light intensity adjustment) C-LL-I		<del></del>	0	
Transmitted illumination (ON/OFF, light intensity adjustment)	<del>_</del>	<del>_</del>	<u></u>	
Aperture stop	<u> </u>	<del>_</del>	0	
Observation method selector (brightfield / darkfield / fluorescence)	<u>—</u>	<u>—</u>	<u></u>	

Note: With NIS-Elements L and F, functions above are not available. Use NIS-Elements D/Br/Ar.

# Camera System

Digital camera system for microscopes "Digital Sight System"

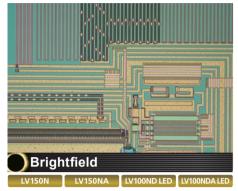




<sup>\*</sup> See the "Digital Camera Digital Sight Series for Microscopes" brochure for details on Digital Sight features.

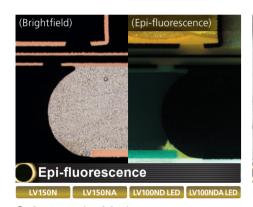
# Observation Methods

Compatible with a wide range of observation / optical contrast methods: In reflected light mode -brightfield, darkfield, polarizing, differential interference, epi-fluorescence, and two-beam interferometry, and in Transmitted light mode- brightfield, darkfield, polarizing, differential interference, and phase contrast.



#### Semiconductors (IC wafers)

From its objective lenses to its illumination systems, the LV-N Series offers thorough measures against flare and provides bright, high-contrast images.



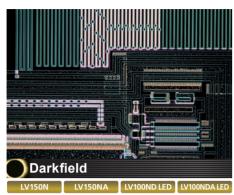
#### Substrate (solder)

The LV-N Series demonstrates superiority in the observation of samples with fluorescent properties, such as organic ELs or mounted substrates.



#### LCD (color filter)

The LV-N Series is effective in the observation of samples with transparency, such as optical components, FPDs, and slide glass samples. When used in conjunction with the C-SP Simple Polarizer and analyzers, transmitted simple polarized observation is possible.



#### Semiconductors (IC wafers)

The use of Nikon's unique concepts in the objective lens darkfield illumination system enables bright darkfield observation and provides high-sensitivity detection of level differences and defects in samples.



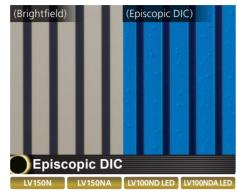
#### **Minerals**

The LV-N Series is effective in the observation of samples with birefringent properties, such as liquid crystals or plastics/glass containing distortion.



#### **Emulsion**

Colorless, transparent samples can be made visible through bright/dark contrast and the use of diffraction and interference, two properties of light.



#### Substrate

Standard-type and high-contrast-type DIC sliders are available to match samples. The LV-N Series is effective for applications such as observation of minute level differences in devices and precision molds.



#### Mica

Michelson (TI) and Mirau (DI) reflection-type twobeam interferometry is possible with the LV-N Series. When used with micrometer eyepieces, minute level differences can be detected and measured without contact with the sample.



#### Nanoparticle (silver)

Colorless, transparent samples can be observed in three dimensions by using polarization to create interference between two beams of light.

# **Specifications**

	LV150N	LV150NA				
Base unit	Maximum sample height: 38 mm (when used with LVNU5A U5A nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) *73 mm when used with one column riser 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 µm/graduation) Stage mounting hole intervals: 70 x 94 (fixed by 4-M4 screw)					
Nosepieces	C-N6 ESD Sextuple Nosepiece ESD LV-NU5 Universal Quintuple Nosepiece ESD LV-NBD5 BD Quintuple Nosepiece ESD LV-NU5I Intelligent Universal Quintuple Nosepiece ESD					
Episcopic Illuminator  LV-UEPI-N  LV-LH50PC 12V50W Precentered Lamphouse, LV-LL LED Lamphouse Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable) Accepts φ 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator						
	LV-UEPI2 LV-LH50PC 12V50W Precentered Lamphouse, LV-LL LED Lamphouse Fluorescence LED Light Source D-LEDI (with light adjustment (PC controllable)) Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), automated optical element switching feature matched to brightfield, darkfield, and epi-fluorescence switch Accepts ø 25 mm filter (NCB11, ND16, ND4), polarizer/analyzer, \( \) plate, excitation light balancer; equipped with noise terminator					
Eyepiece tubes	LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25) LV-TT2 TT2 tilting trinocular eyepiece tube (Erected image, FOV: 22/25) C-TB binocular tube (Inverted image, FOV: 22) P-TB Binocular Tube (Inverted image, FOV: 22) P-TT2 Trinocular Tube (Inverted image, FOV: 22)					
Stages	LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) ESD compatible LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate) ESD compatible LV-S6 6x6 stage (Stroke: 150 x 150 mm) ESD compatible					
Eyepieces	CFI eyepiece series					
Objective lenses	Industrial Microscope CFI60-2/CFI60 optical system Objective lens series: Combinations in accordance with the observation method					
ESD performance	1,000 to 10V, within 0.2 sec. (excluding certain accessories)					
Power consumption	1.2 A / 75 W					
Weight	Approx. 8.6 kg Approx. 8.7 kg					

Weight	Approx. 8.6 kg	Approx. 8.7 kg			
	LV100ND LED	LV100NDA LED			
Base unit	Maximum sample height: 38 mm (when used with LV-NU5 U5 nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 µm/graduation)	Maximum sample height: 33 mm (when used with LVNU5AI U5AI nosepiece and LV-S32 3x2 stage / LV-S64 6x4 stage) 12V50W internal power source for dimmer, coarse and fine adjustment knobs Left: coarse and fine adjustment / Right: fine adjustment, 40 mm stroke Coarse adjustment: 14 mm/turn (with torque adjustment, refocusing mechanism) Fine adjustment: 0.1 mm/turn (1 µm/graduation)			
Nosepieces	C-N6 ESD Sextuple Nosepiece ESD, LV-NU5 Universal Quintuple Nosepiece ESD LV-NBD5 BD Quintuple Nosepiece ESD, LV-NU5I Intelligent Universal Quintuple Nosepiece ESD D-ND6 Sextuple DIC Nosepiece	LV-NU5Al Motorized Universal Quintuple Nosepiece (High-durability motorized 5-hole universal nosepiece)			
Episcopic Illuminators	LV-UEPI-N High color-rendering LED Lamphouse C-LL-I: 50,000 hours of life *1 Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), accepts ø 25 mm filter (LV-C-LCB), polarizer/analyzer; equipped with noise terminator LV-UEPI2 High color-rendering LED Lamphouse C-LL-I: 50,000 hours of life *1 Fluorescence LED light source D-LEDI (with light adjustment (PC controllable)) *option Bright/darkfield switch and linked aperture stop (centerable), field diaphragm (centerable), automated optical element switching feature matched to brightfield, darkfield, and epi-fluorescence switch Accepts ø 25 mm filter (LV-C-LCB), polarizer/analyzer, \(\lambda\) plate, excitation light balancer; equipped with noise terminator	LV-UEPI2A High color-rendering LED Lamphouse C-LL-I: 50,000 hours of life *1 Fluorescence LED light source D-LEDI (with light adjustment (PC controllable)) *option Motorized operation and control of illumination selector turret Motorized aperture stop linked to bright/darkfield selector (automatic optimization matched to objective lens), field diaphragm (centerable) Accepts Ø 25 mm filter (LV-C-LCB), polarizer/analyzer, λ plate, excitation light balancer; equipped with noise terminator			
Diascopic Illuminator	Built-in high color-rendering LED Lamphouse C-LL-I (50,000 hours of life) (Fly Eye optical system) *1 Internal aperture, field diaphragm, filter (45C-LCB); transmitted/reflected selector switch				
Eyepiece tubes	LV-TI3 trinocular eyepiece tube ESD (Erected image, FOV: 22/25), LV-TT2 P-TB Binocular Tube (Inverted image, FOV: 22), P-TT2 Trinocular Tube (Inv				
Stages	LV-S32 3x2 stage (Stroke: 75 x 50 mm with glass plate) / LV-S32SGH slide glass holder LV-S64 6x4 stage (Stroke: 150 x 100 mm with glass plate), LV-SRP P revolving stage NIU-CSRR2 Ni-U right handle rotatable ceramic stage (Stroke: 78 x 54 mm), C-CSR2S right handle stage (Stroke: 78 x 54 mm: Used with stage adapter LV-SAD)				
Condensers	LWD achromat condenser (brightfield), LV-CUD U condenser dry (phase contrast, diascopic DIC, darkfield), Achromat 2x-100x slide condenser (brightfield), DF dry condenser (darkfield), and others				
Eyepieces	CFI eyepiece series				
Objective lenses	Industrial Microscope CFI60-2/CFI60 optical system Objective lens series: Combinations in accordance with the observation method				
ESD performance	1,000 to 10V, within 0.2 sec. (excluding certain accessories)				
Power consumption	0.7 A / 58 W *2 0.7 A / 58 W *2				
Weight	Approx. 9 kg Approx. 10 kg				
*1 Estimated value based on Nikon regulations *2 Reference value based on Nikon regulations					

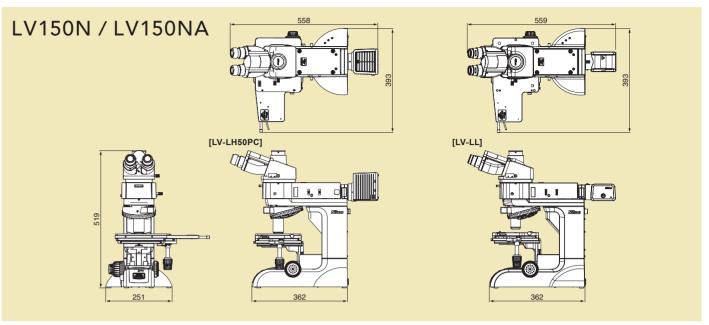
# Lens Specifications

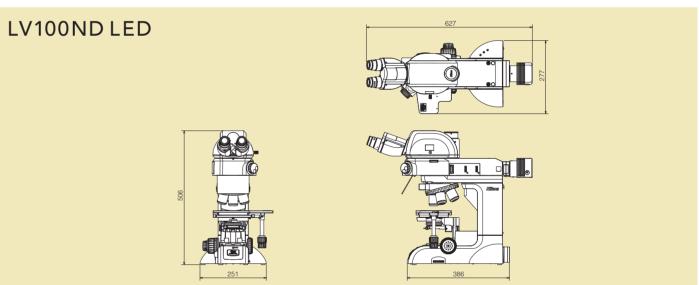
	Туре	Model	Magnification	Product Code No.	NA	Working Distance (mm)
		T Plan EPI	1×	MUE12010	0.03	3.8
		Plan (Achromat)	2.5×	MUE12030	0.075	6.5
		TU Plan Fluor EPI	5×	MUE12050	0.15	23.5
	Brightfield	Universal Plan Fluor (Semi-apochromat)	10×	MUE12100	0.3	17.5
			20×	MUE12200	0.45	4.5
			50×	MUE12500	0.8	1.0
			100×	MUE12900	0.9	1.0
		TU Plan Apo EPI	50×	MUC11500	0.8	2.0
		Universal Plan Apo (Apochromat)	100×	MUC11900	0.9	2.0
			150×	MUC11150	0.9	1.5
		TU Plan Fluor EPI P	5×	MUE13050	0.15	23.5
		Polarizing Universal Plan Fluor	10×	MUE13100	0.3	17.5
	Polarizing	(Semi-apochromat)	20×	MUE13200	0.45	4.5
			50×	MUE13500	0.8	1.0
			100×	MUE13900	0.9	1.0
	Brightfield Long Working Distance	TU Plan EPI ELWD Long Working Distance Universal Plan	20×	MUE21200	0.4	19.0
CF60-2			50×	MUE21500	0.6	11.0
		(Semi-apochromat)	100×	MUE21900	8.0	4.5
	Brightfield Super-long Working Distance	T Plan EPI SLWD Super-long Working Distance Plan (Semi-apochromat)	10×	MUE31100	0.2	37.0
			20×	MUE31200	0.3	30.0
			50×	MUE31500	0.4	22.0
			100×	MUE31900	0.6	10.0
	Brightfield/Darkfield	TU Plan Fluor BD Universal Plan Fluor (Semi-apochromat)	5×	MUE42050	0.15	18.0
			10×	MUE42100	0.3	15.0
			20×	MUE42200	0.45	4.5
			50×	MUE42500	0.8	1.0
			100×	MUE42900	0.9	1.0
		TU Plan Apo BD Universal Plan Apo (Apochromat)	50×	MUC41500	0.8	2.0
			100×	MUC41900	0.9	2.0
			150×	MUC41150	0.9	1.5
	Brightfield/Darkfield	TU Plan BD ELWD	20×	MUE61200	0.4	19.0
	Long Working	Long Working Distance Universal Plan	50×	MUE61500	0.6	11.0
	Distance	(Semi-apochromat)	100×	MUE61900	0.8	4.5

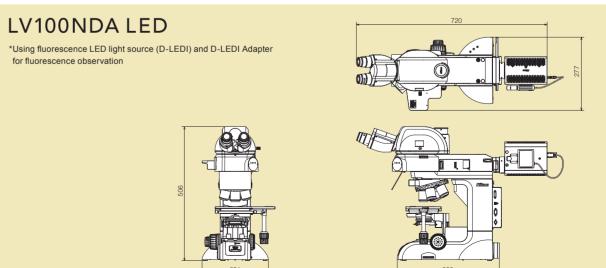
Phase Fresnel lens (diffraction optical element) type
 A circular polarizing plate and depolarizer are built into T Plan EPI 1x/2.5x. (Circular polarizing plate can be attached/detached.)

	Туре	Model	Magnification	Product Code No.	NA	Working Distance (mm)
CFI60	Brightfield With Correction Mechanism	L Plan EPI CR For Inspecting LCDs Plan	20×	MUE35200	0.45	10.9 - 10.0
			50×	MUE35500	0.7	3.9 - 3.0
			100×	MUE35900	0.85	1.2 - 0.85
			100×	MUE35910	0.85	1.3 - 0.95
	Brightfield	L Plan EPI Plan (Achromat)	40×	MUE00400	0.65	1.0
	Brightfield	LU Plan Apo EPI Universal Plan Apo (Apochromat)	100×	MUC00090	0.95	0.4
			150×	MUC10151	0.95	0.3
	Brightfield/Darkfield	LU Plan Apo BD Universal Plan Apo (Apochromat)	100×	MUC40900	0.9	0.51
			150×	MUC50151	0.9	0.42
	Brightfield	LE Plan EPI (Achromat)	5×	MUD00050	0.1	31.0
			10×	MUD00100	0.25	13.0
			20×	MUD00200	0.4	3.6
			50×	MUD00500	0.75	0.5
			100×	MUD00900	0.9	0.31

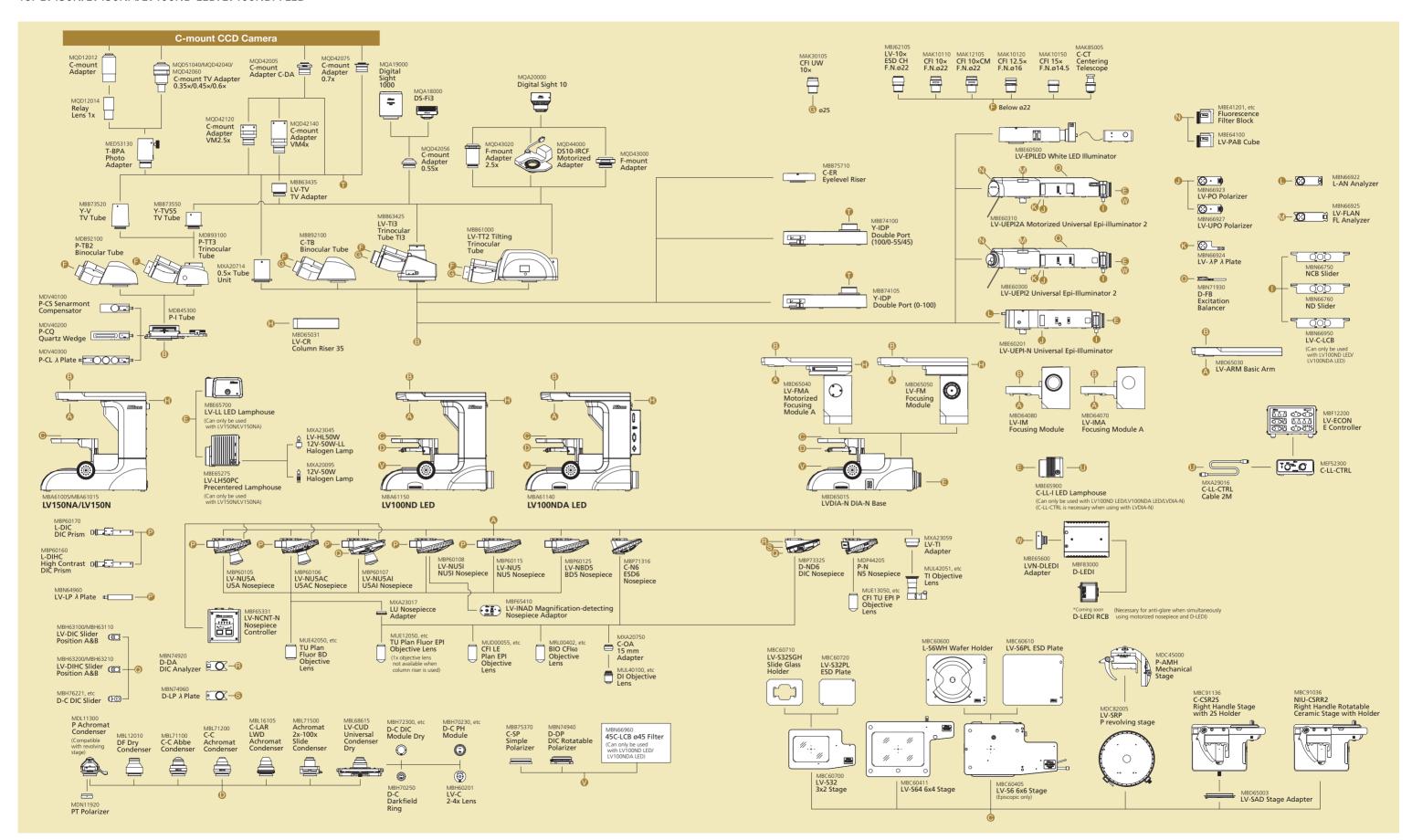
# **Dimensions**







#### for LV150N/LV150NA/LV100ND LED/LV100NDA LED



Specifications and equipment are subject to change without any notice or obligation on the part of the manufacturer. February 2025 @2012-2025 NIKON CORPORATION

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